

ABSTRACT

The present invention discloses a chemically amplified resist composition comprising: a resin
5 which becomes soluble in an aqueous alkali solution in the presence of an acid, a photo acid generator, and an amine derivative which shows, in water of 25°C, such a basicity as to form a conjugate acid and has a medium polarity. The amine derivative acts as a
10 quencher. Therefore, the chemically amplified resist composition of the present invention enables formation of a very precise and fine resist pattern and can be suitably used particularly in a lithography using an ArF excimer laser beam.